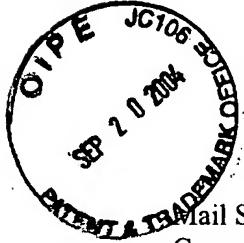


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Mail Stop Amendment
Commissioner For Patents
P.O. Box 1450
Alexandria, VA 22313-1450

September __, 2004

Applicant(s): Timothy R. Piwonka-Corle
Title: Focused Beam Spectroscopic Ellipsometry Method And System
Application No.: 10/716,805 Filing Date: November 18, 2003
Examiner: Rossenberger, R.A. Group Art Unit: 2877
Docket No.: TNCR.059US6 Conf. No.: 8189

Dear Sir:

Transmitted herewith are the following documents in the above-identified application:

- (1) Return Receipt Postcard;
- (2) This Transmittal Letter (1 page)
- (3) Information Disclosure Statement (2 pages);
- (4) PTO Form 1449 (14 sheets); and
- (5) Check for \$180.00.

Please charge any additional fees required and credit any overpayment to our
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Franklin Dyer

Respectfully submitted,

James S. Hsue
Reg. No. 29,545

Date

9/17/04



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Timothy R. Piwonka-Corle
Title: Focused Beam Spectroscopic Ellipsometry Method And System
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Mail Stop Amendment
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Pursuant to 37 C.F.R. §§ 1.56, 1.97 and 1.98, Applicant(s) call(s) the documents listed on the enclosed Form PTO-1449 and copies filed herewith to the Examiner's attention in this patent application.

This application has a filing date after June 30, 2003. Copies of the U.S. Patent(s) and U.S. Published Patent Application(s) documents listed on the accompanying Form PTO-1449 are not enclosed. Copies of the documents listed on the accompanying Form PTO-1449 that are not enclosed were previously submitted in Application No. 09/248,876, from which this Application claims an earlier effective filing date.

Citation of these documents shall not be construed as (1) an admission that the documents are prior art with respect to the invention or inventions claimed in this application, (2) a representation that a search has been made (other than as indicated by any cited document), or (3) an admission that the cited information is, or is considered to be, material to patentability as defined in § 1.56(b).

Attorney Docket No.: TNCR.059US6

Application No.: 10/716,805

09/21/2004 EAREGAY1 00000023 10716805

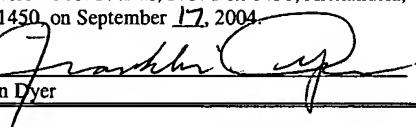
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180.00 OP

This information disclosure statement is submitted under 37 C.F.R. § 1.97(c). A check including \$180.00 for the information disclosure statement fee under 37 C.F.R. § 1.17(p), is enclosed. The Commissioner is authorized, however, to charge any fee that may be required, or to credit any overpayment, against Deposit Account No. 502664. This form is being submitted in duplicate.

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SEP 20 2004		Filing Date	Group
		November 18, 2003	2877

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	3	4,653,908	3/1987	Yajima et al.			
	4	4,653,924	03/31/87	Itonaga et al.			
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	7	4,692,024	09/08/87	Bloss			
	8	4,790,659	12/1988	Erman et al.			
	9	4,810,872	3/7/89	Murakoshi et al.			

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	10	EP652415A1	5/10/9S	Europe					
	11	11342936	5/25/89	Japan			Yes		
	12	2602338A	2/5/88	France			Yes		
	13	63500263	1/28/88	Japan			Abstract		
	14	6332338	2/12/88	Japan			Abstract		
	15	63243836	10/11/88	Japan			Abstract		
	16	2126106	5/15/90	Japan			Abstract		
	17	1132935	5/25/89	Japan			Yes		
	18	214057	1/29/90	Japan			Yes		
	19	2118247	9/21/90	Japan			Abstract		

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	27	5,096,298	03/17/92	Isobe				
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							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
	29	2297008	7/12/90	Japan			Abstract	
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	31	4340404	11/26/92	Japan			Abstract	
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	38	SU987410	5/18/81	U.S.S.R.			Abstract	
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	50	SU1140009A	7/18/83	U.S.S.R.			Abstract		
	51	SU1141297A	10/18/83	U.S.S.R.			Abstract		
	52	SU1157416A	12/26/83	U.S.S.R.			Abstract		
	53	SU1260697A1	7/4/84	U.S.S.R.			Abstract		
	54	SU1369471A	2/28/86	U.S.S.R.			Abstract		
	55	SU1337860A1	9/15/87	U.S.S.R.			Abstract		
	56	SU1571419A1	12/28/87	U.S.S.R.			Abstract		
	57	SU1695145A1	8/3/88	U.S.S.R.			Abstract		

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	93	"Applications of IR Ellipsometric Spectroscopy to Surface Studies," J.D. Fedyk et al., <i>Surface Science</i> , Vol. 234, 1993, pp. 404-424.	
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	122	"Far-infrared ellipsometer," K.L. Barth et al., <i>Rev. Sci. Instrum.</i> , 64(4), April 1993, pp. 870-875.	
	123	"Far-IR spectroscopic ellipsometer," K.-L. Barth et al., <i>Thin Solid Films</i> , Vol. 234, 1993, pp. 314-317.	
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